Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL

MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 1 of 10

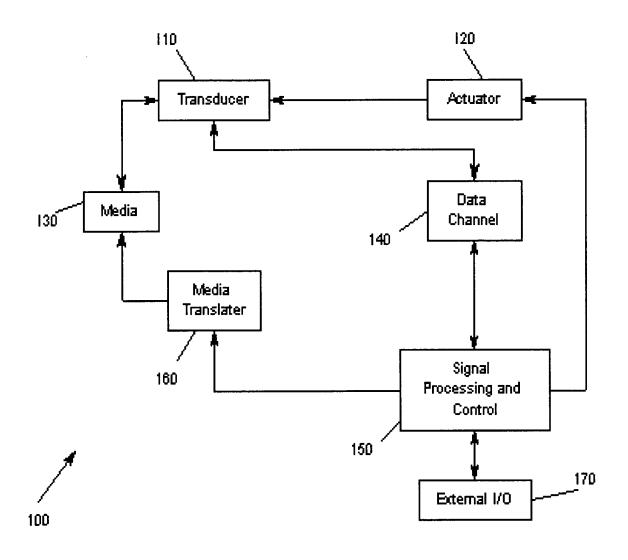


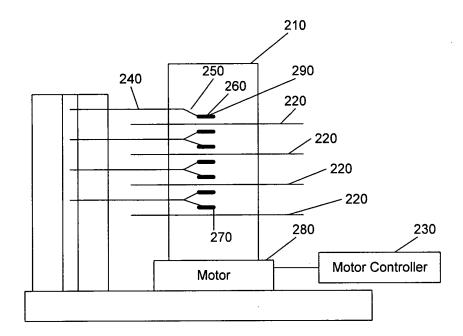
Fig. 1

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al.

Docket: HSJ920030027US1/HITG.025PA

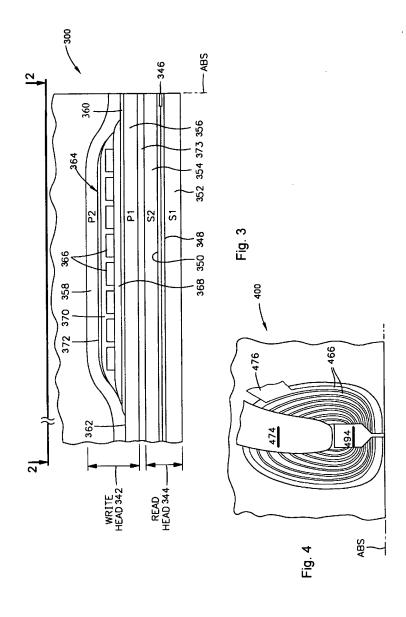
Sheet 2 of 10



200

Fig. 2

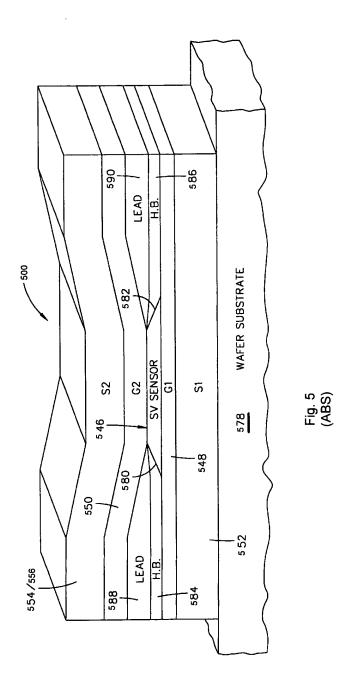
Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA Sheet 3 of 10



Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 4 of 10



Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL

MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 5 of 10

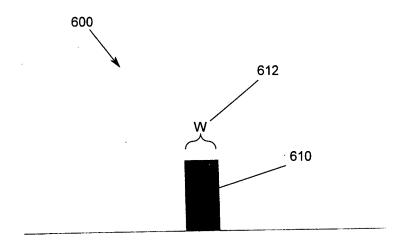


Fig. 6

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 6 of 10

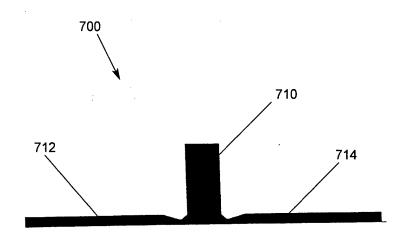


Fig. 7

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL

MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 7 of 10

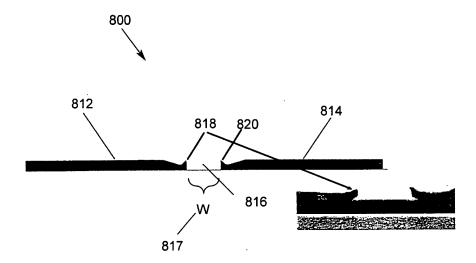


Fig. 8

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al.
Docket: HSJ920030027US1/HITG.025PA
Sheet 8 of 10

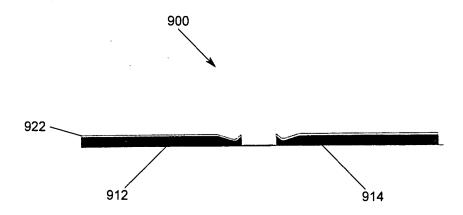


Fig. 9

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL MECHANICAL POLISHING AND SENSOR FORMED THEREWITH Applicants: Cyrille, et al. Docket: HSJ920030027US1/HITG.025PA

Sheet 9 of 10

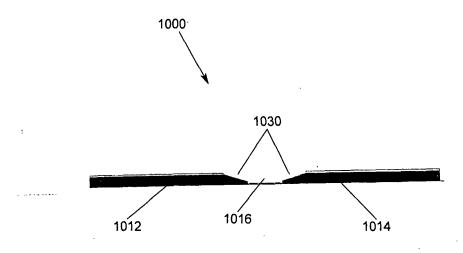


Fig. 10

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS USING A SINGLE LAYER RESIST AND CHEMICAL

MECHANICAL POLISHING AND SENSOR FORMED THEREWITH

Applicants: Cyrille, et al.
Docket: HSJ920030027US1/HITG.025PA

Sheet 10 of 10

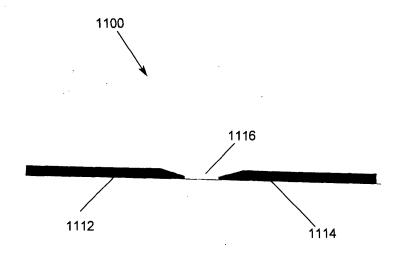


Fig. 11